SUPPLEMENTARY MATERIAL

DOI: 10.1039/b000000y

Fig. S1 Scanning electron micrographs showing photoresist overburden removal by timed UV exposure (shown in seconds) for chevrons grown at $\alpha = 85^\circ$ with noticeable overburden. Scale bar indicates 1 $\mu$m.

Fig. S2 Scanning electron micrographs showing (a) side and (b) top views of the vertical post nanostructured thin film used for separating DNA. Scale bars indicate 1 $\mu$m.
Fig. S3 10 kbp and 48 kbp DNA separation was highest at a frequency of \( \sim 2 \) Hz and angle of 13.5°. Separation angles were measured 2 mm from the injection point. The error bars indicate upper and lower bound measurements of the separation angle.